

## CONTENTS

Preface	vii
Conference organisation	ix
Supporting organisations and sponsors	x

### PART I. PRECURSORS FOR SURFACE PROCESSING

New metallo-organic precursors for surface processing D.C. Bradley	1
Design and synthesis of CVD precursors to thin film ceramic materials L.V. Interrante, B. Han, J.B. Hudson and C. Whitmarsh	5
The photolytic laser chemical vapor deposition rate of platinum, its dependence on wavelength, precursor vapor pressure, light intensity, and laser beam diameter D. Braichotte, C. Garrido and H. van den Bergh	9
Photoprocesses in organometallics R. Larciprete	19
Preferential (111) orientation of ZnSe on (100) GaAs deposited by laser-induced MOCVD J. Simpson and J.O. Williams	27
The adsorption of triethylgallium on GaAs(100) at 300 K: adsorption kinetics from optical second harmonic generation transients M.E. Pemble, J.T. Allen, D.S. Buhaenko, S.M. Francis, P.A. Goulding, J. Lee and M.J. Parrott	32
Photoreactions of adsorbed CH <sub>3</sub> Br on Pt(111) G. Radhakrishnan, W. Stenzel, H. Conrad and A.M. Bradshaw	36
Second harmonic generation of CO <sub>2</sub> -laser radiation and FTIR spectroscopy for resonant desorption in the adsorbate CO-NaCl(100) J. Heidberg, B. Brase, K.-W. Stahmer and M. Suhren	44

### PART II. DEPOSITION

#### II-1. SUPERCONDUCTORS

High- $T_c$ YBa <sub>2</sub> Cu <sub>3</sub> O <sub>7-<math>\delta</math></sub> prepared by chemical vapour deposition F. Schmaderer, R. Huber, H. Oetzmann and G. Wahl	53
Deposition, characterization, and laser ablation patterning of YBCO thin films P. Vase, Shen Yueqiang and T. Freltoft	61
Computer-controlled ion beam deposition systems for high $T_c$ superconductor and other multi-component oxide thin films and layered structures A.R. Krauss, O. Auciello, A.I. Kingon, M.S. Ameen, Y.L. Liu, T. Barr, T.M. Graettinger, S.H. Rou, C.S. Soble and D.M. Gruen	67
High quality YBa <sub>2</sub> Cu <sub>3</sub> O <sub>x</sub> ultra-thin films and Y/Pr/Y multilayers made by a modified RF-magnetron sputtering technique J. Gao, W.A.M. Aarnink, G.J. Gerritsma and H. Rogalla	74
Characterization of the KrF laser-induced plasma plume created above an YBaCuO superconducting target and preparation of superconducting thin films C. Girault, D. Damiani, C. Champeaux, P. Marchet, C. Germain, J.P. Mercurio, J. Aubreton and A. Catherinot	78

Laser-ablation deposition of uniform thin films of $\text{Bi}_2\text{Sr}_2\text{CaCu}_2\text{O}_x$ A. Sajjadi, K. Kuen-Lau, F. Saba, F. Beech and I.W. Boyd	84
An investigation of laser ablation and deposition of Y-Ba-Cu-O in an oxygen environment P.E. Dyer, A. Issa and P.H. Key	89
 II-2. METALS	
Simulation of laser CVD G. Wahl and H. Esrom	96
Gas-phase transport and kinetics in pulsed-laser CVD L. Konstantinov, R. Nowak and P. Hess	102
High performance contact formation in LSI circuit restructuring using visible pulse laser induced ablation and CVD Y. Morishige, S. Kitamura and S. Kishida	108
Laser-assisted deposition for electronic packaging applications A. Bauer, J. Ganz, K. Hesse and E. Köhler	113
Multichip packaging for very-high-speed digital systems A.F. Bernhardt, A.T. Barfknecht, R.J. Contolini, V. Malba, S.T. Mayer, N.F. Raley and D.B. Tuckerman	121
Optimization of the laser-induced deposition technique for its application in X-ray mask repair R. Putzar, H.-C. Petzold and H. Staiger	131
HF formation in laser-induced CVD of tungsten A.J.P. van Maaren, R.L. Krans and W.C. Sinke	138
Laser direct writing of copper on various thin-film substrate materials H.G. Müller, K. Buschick, S. Schuler and A. Paredes	143
Direct writing of conducting traces by chemical modification of solid coatings with laser radiation M. Bode, E.W. Kreutz and M. Krösche	148
VUV synchrotron radiation processing of thin palladium acetate spin-on films for metallic surface patterning Y. Zhang and M. Stuke	153
Investigation of the mechanism of the UV-induced palladium deposition process from thin solid palladium acetate films H. Esrom and U. Kogelschatz	158
Laser evaporation of metal sandwich layers for improved IC metallization R. Pielmeier, D. Bollmann and K. Habberger	163
 II-3. INSULATORS AND REFRACTORY MATERIALS	
Filling of Si oxide into a deep trench using digital CVD method Y. Horiike, T. Ichihara and H. Sakaue	168
Photo-assisted deposition of thin films on III-V semiconductors with UV and IR lamps Y.I. Nissim, J.M. Moison, F. Houzay, F. Leblanc, C. Licoppe and M. Bensoussan	175
$\text{SiO}_2$ deposition by direct photolysis at 185 nm of $\text{N}_2\text{O}$ and $\text{SiH}_4$ M. Petitjean, N. Proust, J.-F. Chapeaublanc and J. Perrin	189
Deposition of $\text{SiO}_2$ by reactive excimer laser ablation from a $\text{SiO}$ target E. Fogarassy, A. Slaoui, C. Fuchs and J.P. Stoquert	195
Sol-gel low-temperature preparation of silica films: RBS, TEM and MOS C-V characterization A. Boelle, J.A. Roger, B. Canut, J. Mugnier and M. Pitaval	200
Gas mixture dependence of the LCVD of $\text{SiO}_2$ films using an ArF laser T. Szörényi, P. González, D. Fernández, J. Pou, B. León and M. Pérez-Amor	206

Excimer laser deposition of silica films: a comparison between two methods B. León, A. Klumpp, M. Pérez-Amor and H. Sigmund	210
Photochemical vapor deposition of titaniumdiboride J. Elders, D. Bebelaar and J.D.W. van Voorst	215
In situ formation of ionic carbide clusters by laser ablation R. Teghil, A. Giardini-Guidoni, S. Piccirillo, A. Mele and F. Polla-Mattiot	220
Synthesis of ultrafine TiO <sub>2</sub> powders by a CW CO <sub>2</sub> laser F. Curcio, M. Musci, N. Notaro and G. De Michele	225
<b>II-4. SEMICONDUCTORS</b>	
On the role of the substrate position in the CO <sub>2</sub> laser CVD of amorphous hydrogenated silicon E. Golusda, R. Lange, G. Mollekopf and H. Stafast	230
Laser CVD of a-Si:H from SiH <sub>4</sub> and Si <sub>2</sub> H <sub>6</sub> : relations between chemistry, growth rate and film properties K. Hesch, P. Hess, H. Oetzmam and C. Schmidt	233
Picosecond YAG laser photoablation of amorphous silicon W. Marine, J.M. Scotto D'Aniello and J. Marfaing	239
The influence of deposition parameters on the growth of a-SiGe:H alloys in a plasma CVD system M. Zeman, I. Ferreira, M.J. Geerts and J.W. Metselaar	245
Good-quality Ge films grown by excimer laser deposition C.N. Afonso, R. Serna, F. Catalina and D. Bermejo	249
<b>PART III. DESORPTION, ABLATION, ETCHING AND PATTERNING</b>	
Industrial laser applications F.G. Bachmann	254
Surface modifications of Kapton and cured polyimide films by ArF excimer laser: applications to imagewise wetting and metallization H. Hiraoka and S. Lazare	264
Excimer laser ablation of polyimide G. Ulmer, B. Hasselberger, H.-G. Busmann and E.E.B. Campbell	272
Photochemically assisted laser ablation of doped polymethyl-methacrylate M. Bolle, K. Luther, J. Troe, J. Ihlemann and H. Gerhardt	279
Picosecond time-resolved laser desorption N. Eleftheriadis, H.-P. Ludescher, M. Süßbauer and D. von der Linde	284
Mechanisms of photon-stimulated desorption and chemisorption of atomic particles on the surfaces of semiconductors and metals A.I. Agafonov and T.M. Makhviladze	288
Surface temperature measurements using pyrometry during excimer laser pulsed etching of silicon in a Cl <sub>2</sub> environment T.S. Baller, J.C.S. Kools and J. Dieleman	292
Reactive ion beam etching of Si/SiO <sub>2</sub> systems using SF <sub>6</sub> /O <sub>2</sub> chemistry D. Korzec, T. Kessler and J. Engemann	299
On the two- and three-dimensional simulation of ion-milled structures H.M. Hütten, K.-D. Raddatz, M.K. Sharma and J. Engemann	306
Spectroscopic study of the plasma created by interaction between a TEA CO <sub>2</sub> laser beam and a Ti target in a cell containing helium gas J. Hermann, C. Boulmer-Leborgne and B. Dubreuil	315
Luminescence and ESCA analysis of laser-ablated materials A. Giardini-Guidoni, A. Morone, M. Snels, E. Desimoni, A.M. Salvi, R. Fantoni, W.C.M. Berden and M. Giorgi	321

## PART IV. PHOTON AND ION SURFACE MODIFICATIONS

Controlled structuring of polymer surfaces by UV-laser irradiation W. Kesting, T. Bahners and E. Schollmeyer	326
Ion-beam-assisted formation of interconnections into high temperature polymers J. Davenas, G. Boiteux, J.M. Bureau and D. Brousseau	330
Laser-induced photochemical adherence enhancement J. Breuer, S. Metev, G. Sepold, O.-D. Hennemann, H. Kollek and G. Krüger	336
Applications of doping and dedoping of Teflon AF films in microfabrication using KrF and ArF excimer lasers H. Hiraoka and S. Lazare	342
Ultra-flat p-n junctions formed by solid source laser doping G. Stock, D. Bollmann, R. Buchner, G. Neumayer and K. Habberger	348
Low temperature VUV enhanced growth of thin silicon dioxide films P. Patel and I.W. Boyd	352
Chemical reactions at solid-solid interfaces induced by pulsed laser annealing E.J. Petit and R. Caudano	357
Nitridation of titanium by multipulse excimer laser irradiation E. D'Anna, G. Leggieri, A. Luches, M. Martino, A.V. Drigo, G. Majni, P. Mengucci and I.N. Mihailescu	365
Annealing kinetics during rapid thermal processing of excimer laser-induced defects in virgin silicon B. Hartiti, A. Slaoui, J.C. Muller and P. Siffert	371
Influence of the substrate on the temperature induced by pulsed laser irradiation of thin films A. Jadin, I.V. Filiouguine, M. Wautelet and L.D. Laude	375
Pulsed excimer and Nd:YAG laser crystallization of a-Si:H. The specific role of hydrogen M. Elliq, E. Fogarassy, J.P. Stoquert, C. Fuchs, S. de Unamuno, B. Prévot and H. Pattyn	378
The influence of the substrate on the transformations induced in Si by nanosecond laser irradiation: a time-resolved study J. Solis, C.N. Afonso and F. Catalina	383
Investigation of laser recrystallization of thin Si films using numerical simulation B. Hu, A. Seidl, R. Buchner, D. Bollmann, W. van der Wel and K. Habberger	388
Time-resolved TEM of laser-induced structural changes in GeTe films O. Bostanjoglo and P. Thomsen-Schmidt	392
Thermal evolution of W/Si and W/C multilayers under pulsed laser heating and classical annealing V. Dupuis, M.F. Ravet, C. Tête and M. Piecuch	398
Diffusion and microstructures induced by excimer laser irradiation in Ge-Sb thin film bilayers R. Serna, C.N. Afonso, F. Catalina, N. Teixeira, M.F. da Silva and J.C. Soares	405
Morphological improvement of zinc electrodeposits by laser assistance I. Zouari, M. Calvo, F. Lapicque and M. Cabrera	411
CW laser-induced transformation of thin Sb, Se and Sb <sub>2</sub> Se <sub>3</sub> films in air K. Kolev, M. Wautelet and L.D. Laude	418
Instability and structural transformation of amorphous ultra-thin W-Si multilayer structures during heavy ion irradiation J. Marfaing, W. Marine, B. Vidal, M. Toulemonde, M. Hage Ali and J.P. Stoquert	422
Crystallization of Fe-Zr metallic glasses during ion irradiation L.-U.A. Andersen and J. Böttiger	427
Glass surface treatment with excimer and CO <sub>2</sub> lasers C. Buerhop, B. Blumenthal, R. Weissmann, N. Lutz and S. Biermann	430



**PART V. ADVANCED TECHNIQUES OF CHARACTERISATION**

Hydrogen plasma treatment of silicon surfaces studied by in-situ spectroscopic ellipsometry P. Raynaud, J.P. Booth and C. Pomot	435
Scanning tunneling microscopy and technical applications H. Strecker and G. Persch	441
Femtosecond transient reflectivity measurements as a probe for process-induced defects in silicon A. Esser, W. Kütt, M. Strahnen, G. Maidorn and H. Kurz	446
In situ silicon solid state regrowth kinetics measurement in a rapid thermal processor J.-M. Dilhac, N. Nolhier and C. Ganibal	451
Author index	455
Subject index	461